

Form PTO-1449

Document Number (Optional)

Application Number

HTIRC-02-013

10/660,914

Applicant

Chao-Peng Chan et al.

Filing Date

09/12/03

Group Art Unit

INFORMATION DISCLOSURE CITATION
IN AN APPLICATION

(Use several sheets if necessary)

U. S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	NUMO DATE IF APPROPRIATE
Chy	5310626	5/10/94	Fernandes et al.	430	327	3/1/93
Chy	6504675	1/7/03	Shukh et al.	360	125	1/12/01
Chy	6255035	7/3/01	Minter et al.	430	312	3/17/99
Chy	4238559	12/9/80	Feng et al.	430	156	8/24/78

FOREIGN PATENT DOCUMENTS

DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
					YES	NO

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER

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Aug -	Chemistry of a Chemically Amplified Negative Resist and Process Modification for Electron Beam Exposure, by Shigeki Yamamoto et al., Presented by Patrick Martens, Sumitomo Chemical America.
Aug -	Perpendicular Recording Head Technology, DASCAM Business Group, TDK Corp., Japan, 07/23/02, p.5.

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Curry
"Bake Condition Effect on Hybrid Lithography Process for Negative Tone Chemically Amplified Resists", by L. Pain et al. Advances in Resist Technology and Processing XVII, Francis M. Houlihan, Editor, Proc. of SPIE, Vol. 3999 (2000), 0277-786X/00.

Ch. 1

5/2006

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